UNITED STATES PATENT AND TRADEMARK OFFICE **CERTIFICATE OF CORRECTION**

PATENT NO.

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Page 1 of 1

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INVENTOR(S)

: Derraa et al.

It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

At Column 8, Line 2, in Claim 10, after "region," please add -- wherein a substantial portion of the titanium silicide is interspersed in the titanium before the conductive contact layer is deposited on the upper surface of the silicon substrate over the junction region, --

Signed and Sealed this

Twenty-ninth Day of August, 2006

JON W. DUDAS Director of the United States Patent and Trademark Office